

## 1 IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

2 priority Application Serial No. .... 08/984,730  
3 priority Filing Date ..... December 4, 1997  
4 Inventor ..... D.G. Custer et al.  
5 Assignee ..... Micron Technology, Inc.  
6 priority Group Art Unit ..... 3723  
7 priority Examiner ..... L. Wilson  
8 Attorney's Docket No. ..... MI22-1172  
Title: Polishing Systems, Methods Of Polishing Substrates, and Methods Of Preparing  
9 Liquids For Semiconductor Fabrication Processes

7  
8 **PRELIMINARY AMENDMENT**

9 To: Assistant Commissioner for Patents  
10 Washington, D.C. 20231

11 From: David G. Latwesen (Tel. 509-624-4276; Fax 509-838-3424)  
12 Wells, St. John, Roberts, Gregory & Matkin P.S.  
13 601 W. First Avenue, Suite 1300  
14 Spokane, WA 99201-3817

15 **AMENDMENTS**16 **In the Specification**

17 At p. 1, before the "Technical Field" section, insert

18 **RELATED PATENT DATA**

19 This patent resulted from a divisional application of U.S. Patent  
Application Serial No. 08/984,730, which was filed on December 4, 1997.

20 **Amended Claims**

21 Cancel claims 6-38.